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(54) **SOURCE VESSEL FOR EUV**

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(57)

ABSTRACT

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A source vessel for extreme ultraviolet (EUV) includes a body that includes an outlet for discharging tin debris disposed in a central portion and an intermediate focus (IF) disposed in an upper end portion, and a reflector disposed in a lower end of the body and that includes a through-hole through which laser light passes. The body includes an IF cap portion disposed on a lower portion of the intermediate focus and that includes a heater disposed on an outer surface thereof, and an IF scanner portion disposed on an upper portion of the intermediate focus and that includes a cooling pipe disposed on an external surface thereof. An inner surface of the IF cap portion includes a flow groove through which tin residue flows, and the source vessel further includes a collection container connected to the flow groove.

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